

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>				Docket Number (Optional) CS02-096		Application Number	
				Applicant(s) Lin et al.			
				Filing Date		Group Art Unit	

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		US 6,410,191B1		Nistler et al.			
		US 5,766,829		Cathey, Jr. et al.			
		US 6,458,495B1		Tsai, et al.			
		US 6,355,399b1		Sajan et al.			
		6,482,554		Matsunuma			

FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>	
	S. Vaidya, Phase-Shifting Photomasks, Semiconductor fabtech, Edition 1, Issued September 1994, S. Vaidya, AT&T Bell Laboratories, Murray Hill, New Jersey, USA, Website: http://www.semiconductorfabtech.com/features/lithography/articles/body1.171.php3 , 5/7/03
	John S. Petersen, et al., Development of a Sub-100nm Integrated Imaging System Using Chromeless Phase-Shifting Imaging with Very High NA KrF Exposure and Off-axis Illumination, found on website; http://www.advlitho.com/content/Papers/SPIE_microlith_02/4691-50_Petersen_Conley_et_al.pdf , May 8, 2003 , discusses Chromeless Phase shift mask techniques.

EXAMINER	DATE CONSIDERED 7-6-05
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

